## **Solitec High Speed Spin Processor**

## Prestart Checklist

1. Check that DI Water is turned on. (See DI-Water manual posted in Service Bay wall)







2. Open nitrogen (N2) gas valve. 3. Turn main power switch ON

4. Vacuum pressure at least 18 inch Hg. (gauge located on wall right of spinner)

## **Procedure**

- 1. Open spinner safety cover.
- 2. Carefully center wafer (face-up) on the vacuum stage spindle.
- 3. Press POWER (A) button.
- 4. Press VACUUM (B) button. Note: VACUUM indicator (C) goes out when vacuum is ON.
- 5. Close safety cover. Note: Spinner only operates when cover is closed.
- 6. Test-spin wafer by pressing START button (D) and adjust speed (F) as indicated on display (G).

Note: 4kRPM is typical.

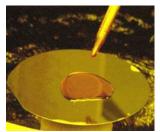
- 7. Observe through safety cover hole that the wafer is balanced properly. If wafer spins correctly go to step 8. If not, press STOP button (H). Once wafer stops spinning open safety cover, press VACUUM button (B) to release the wafer, and recenter the wafer. Continue from step 4.
- 8. Press the STOP (G) button.
- 9. Open safety cover.
- **10.** Set spin time using  $(\mathbf{E})$ .
- **11.** Squeeze 1 evedropper-full of photoresist onto center of wafer, about size of a quarter. (Typical for 4" dia. wafers)
- **12.** Close spinner safety cover.
- **13.** Press START (**D**) button. Wait for spinner to stop.
- 14. Open spinner safety cover.
- **16.** Press VACUUM (A) button to release spindle vacuum. Carefully remove wafer.



Safety Cover and Spindle



Main Control Panel



Use eye dropper to apply photoresist in center of wafer.